

JUN 15 2006

PATENT
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the **PATENT APPLICATION** of:

Ching-Wei Lin

Application No.: 10/767,665

Confirmation No.: 5412

Filed: January 29, 2004

For: PROCESS FOR FORMING
POLYCRYSTALLINE SILICON LAYER BY
LASER CRYSTALLIZATION

Group: 2813

Examiner: Stephen W. Smoot

Our File: TET-PT049

Date: June 15, 2006

**RESPONSE TO NON-COMPLIANT
AMENDMENT PURSUANT TO 37 C.F.R. 1.121**

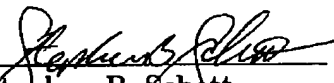
Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Enclosed is the signed amendment.

Respectfully submitted,

Ching-Wei Lin

By 
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REPLY PURSUANT TO 37 C.F.R. § 1.116

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This Reply is being filed in response to the February 17, 2006 Office Action, and submitted with a petition for one month time extension; an earlier signed amendment was apparently not received by the USPTO.

Please amend the application without prejudice or disclaimer as follows.